

From R&D to Thin Film Silicon PV at Oerlikon Solar

3rd Gen Photovoltaics: CleanTech Day
CSEM Basel / 19th August 2009

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CH-2000 Neuchâtel

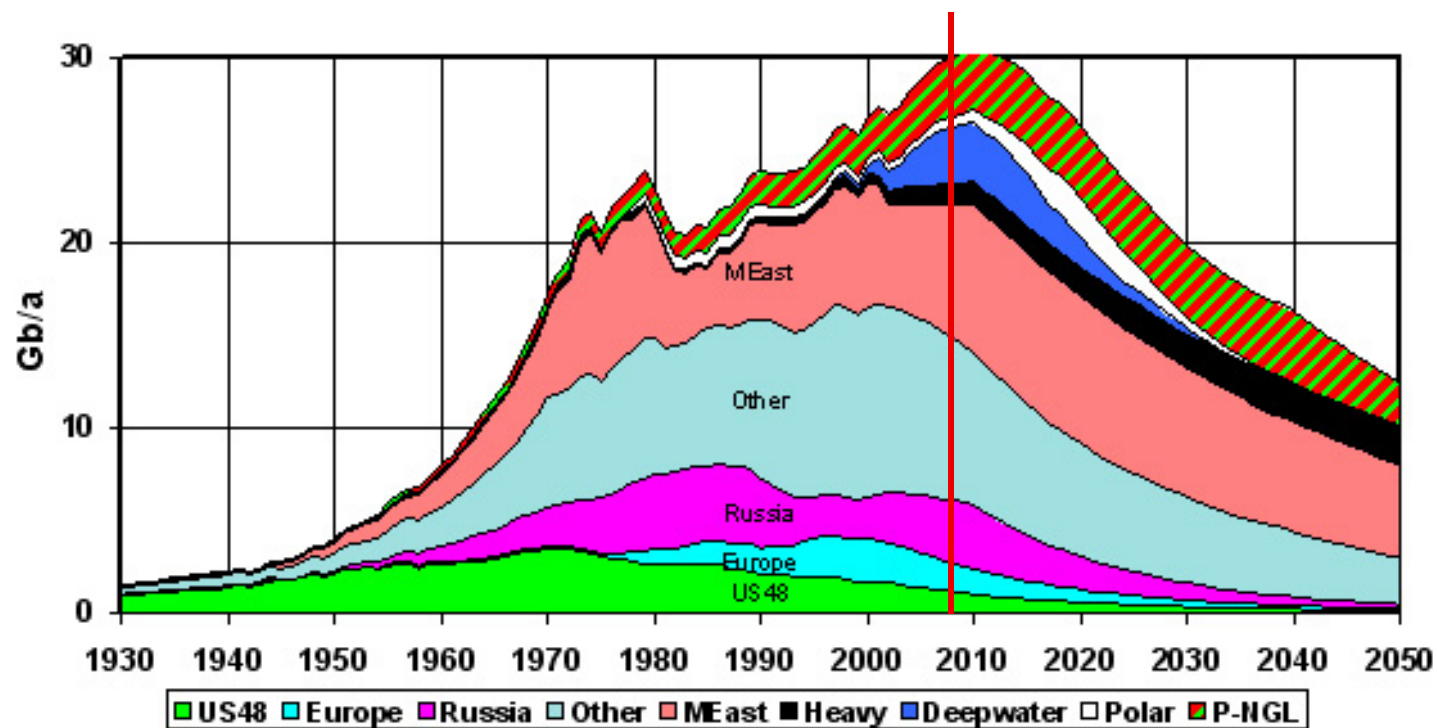


Agenda

1. Why Solar?
2. History IMT - Oerlikon Solar
3. Oerlikon Solar: R&D tasks and results
4. Proven Thin Film Manufacturing Solutions
5. Perspectives & Opportunities

The Need for Renewable Energies

Regular Oil & Natural Gas Liquids
2003 Base Case Scenario



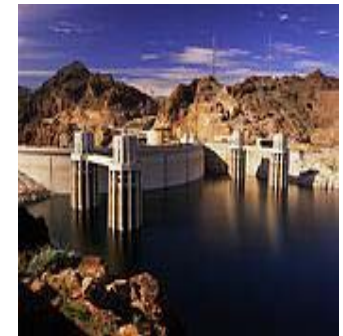
The end of
the oil era

Source: Uppsala Hydrocarbon Depletion Study Group

Renewable Energy Options

Sun	120,000.0 TW
Geothermal	12.0 TW
Wind	3.0 TW
Tide and ocean currents	2.0 TW
Hydroelectric	0.5 TW

Solar has greatest potential to meet world's growing electricity needs compared to other renewable energy sources



Source: Engineering and Science No. 2 2007

Two cell technologies

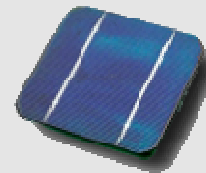
Technology

Substrate

Cell

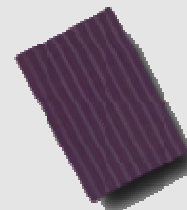
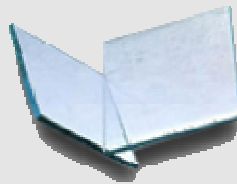
Issues

Crystalline
Silicon



Cost
Silicon Supply

Thin Films



Large Scale
Efficiency

Option: Thin film silicon

A little bit of history....to achieve to

Oerlikon Solar

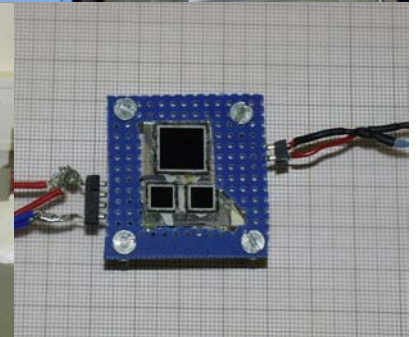
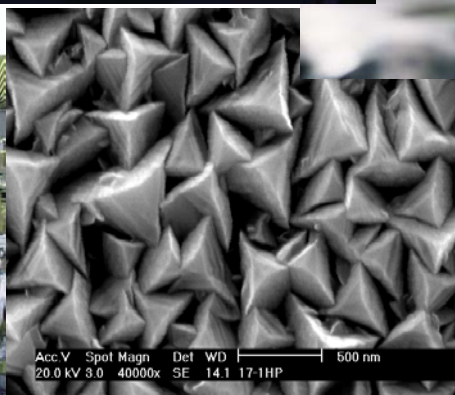
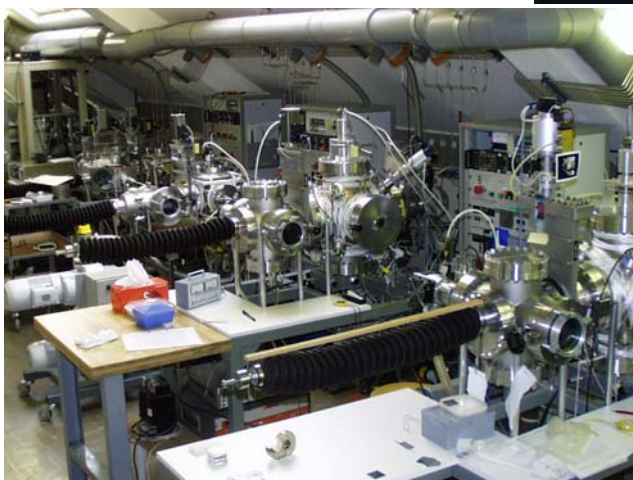
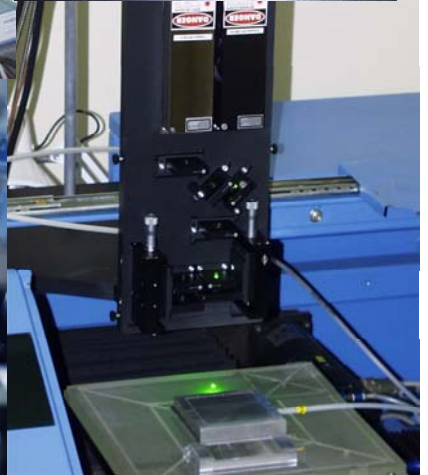
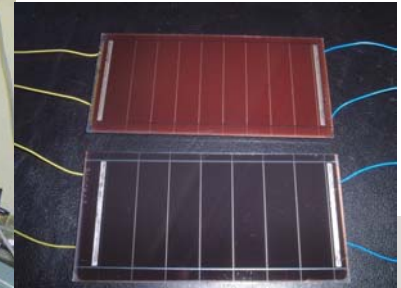


IMT in the early days.....

oerlikon
solar



institut de microtechnique
université de neuchâtel



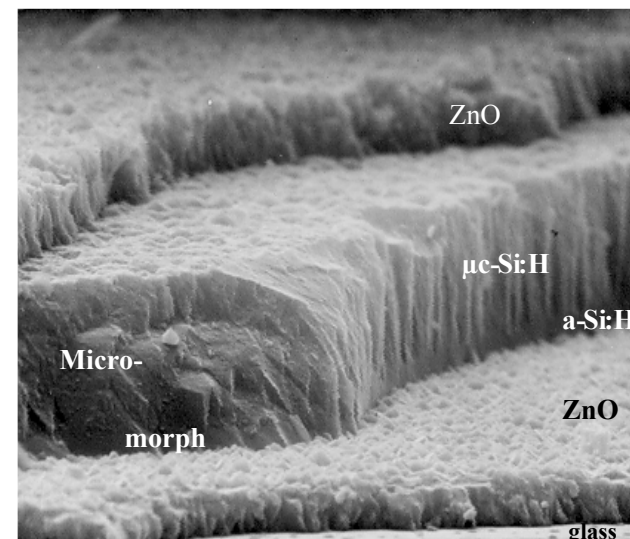
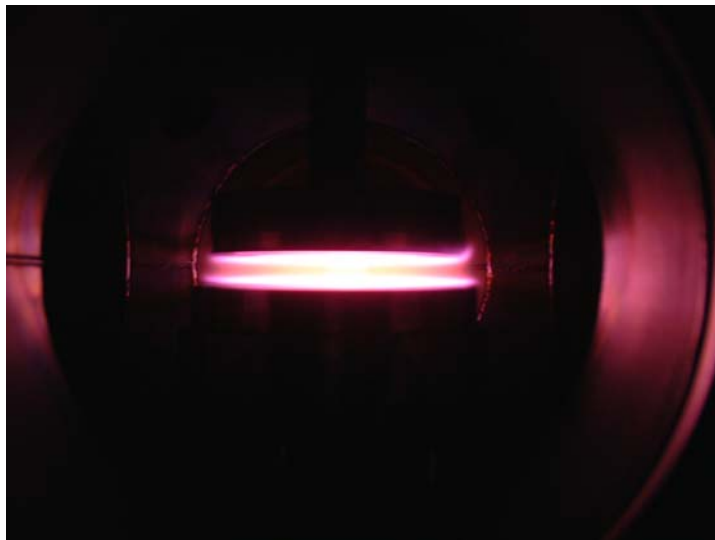
Courtesy of IMT-NE

Kroll / 3rd Gen Photovoltaics: CleanTech Day; 19th August 2009

Roots: Long-term research at IMT Neuchâtel

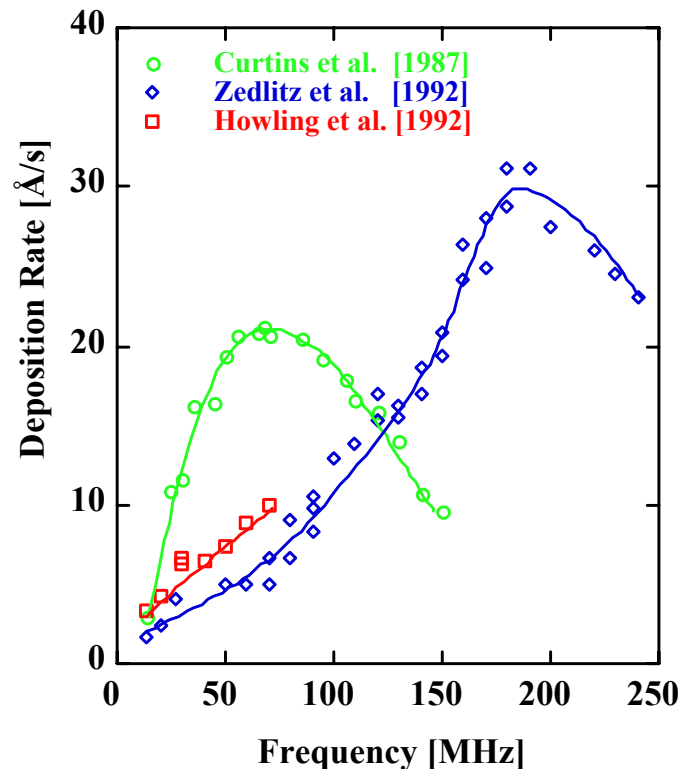
Very promising concepts (cost reduction & efficiency)

- 1987: Introduction of VHF-GD PECVD deposition
- 1994: Introduction of “Micromorph” concept
- LPCVD ZnO for advanced light-trapping



Courtesy of IMT-NE

Deposition Rates vs. Plasma Excitation Frequency



Deposition rate increase has been reproduced and confirmed by other R&D groups

- **no electrical artefact**
- **hence, real plasma effect**
- **position of rate maximum due to electrical losses in system**

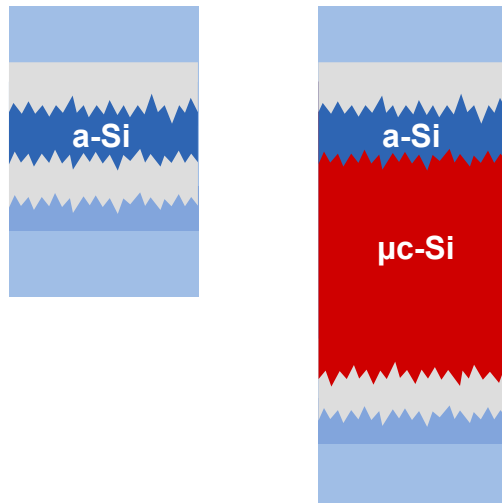
Curtins et al., Elec. Lett 23 (1987) 228

Zedlitz et al., MRS Symp. Proc. 258 (1992) 147

Howling et a., J. Vac. Sci. Technol. A 10 (1992) 1080

U. Kroll et al., Sol. Ener. Mat. & Sol. Cells 48 (1997) 343.

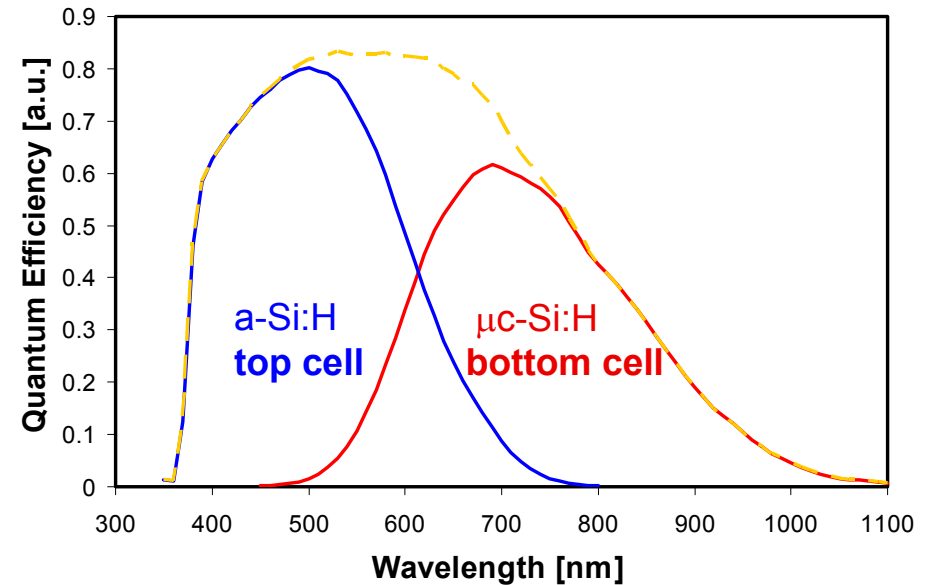
Micromorph[®] Process Technology



Amorph
Single
Junction

Micromorph[®]
Tandem
Junction

More Energy Absorbed



← Visible → ← Near IR →

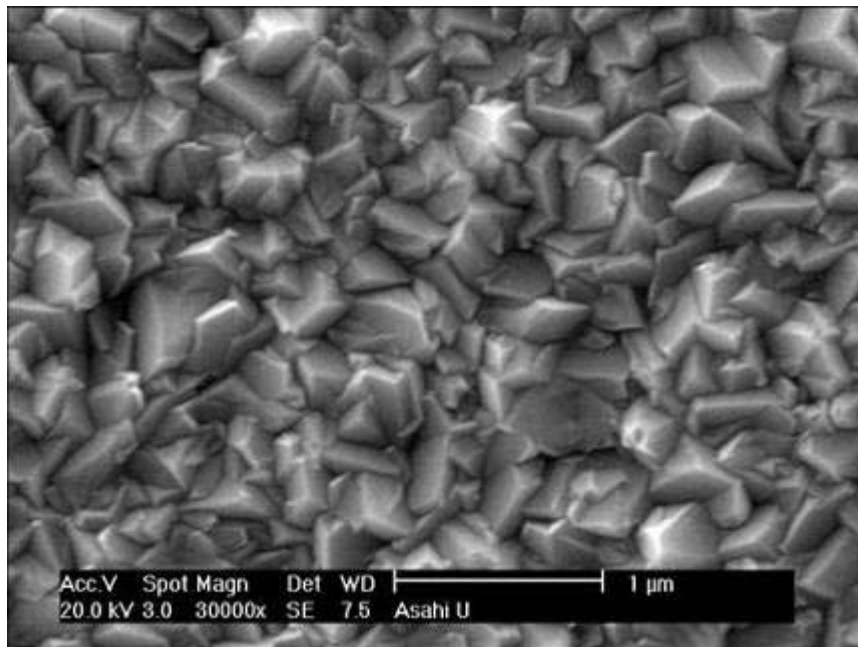
Amorph

Micromorph[®] Tandem

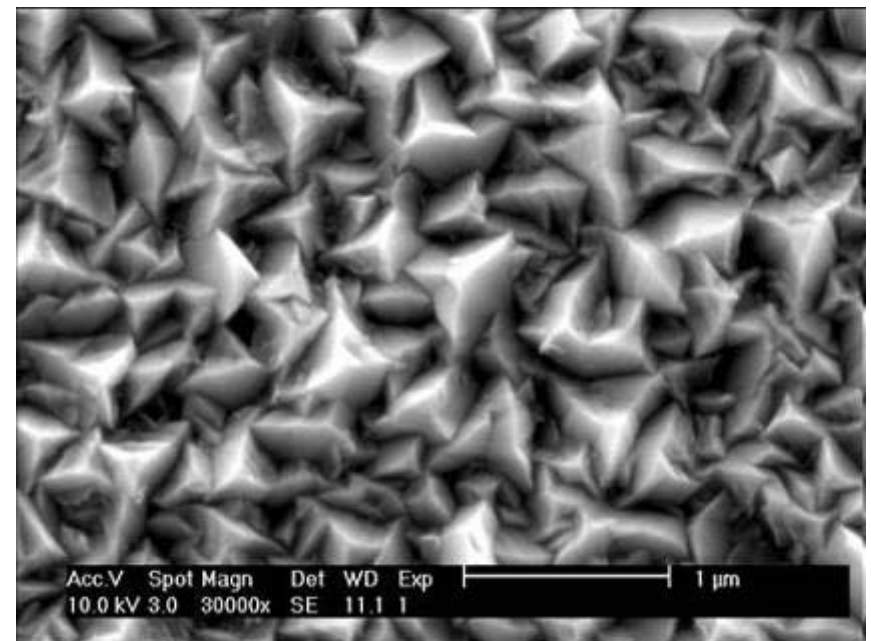
Light-trapping – fundamental for thin film Si solar cells:

Key issue TCO: **approach by LPCVD ZnO**

Asahi U



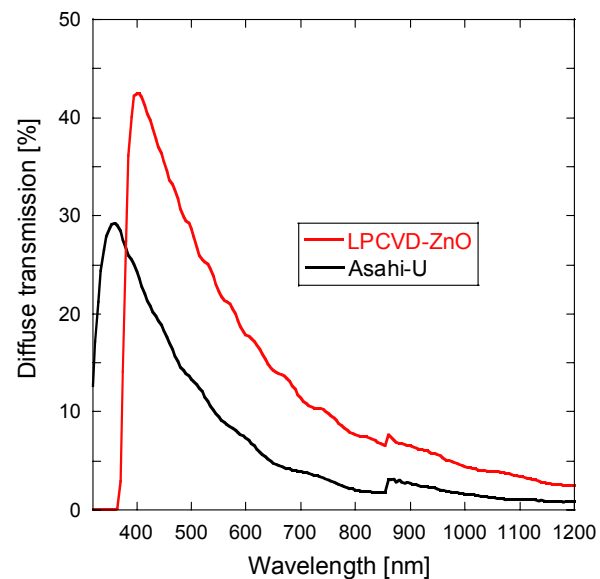
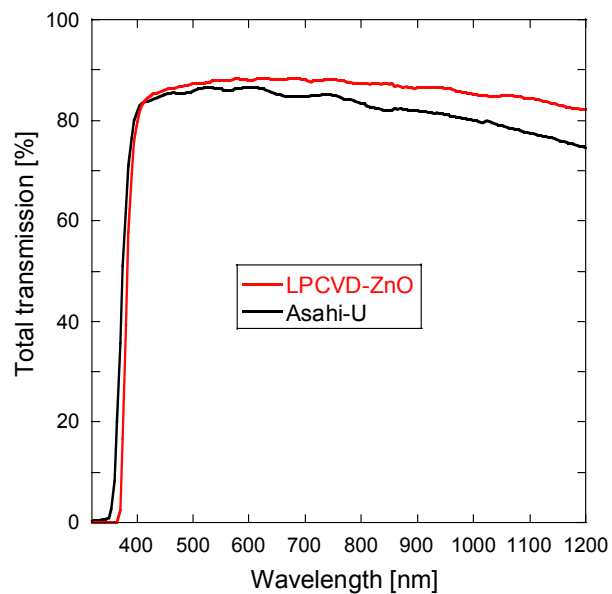
LPCVD ZnO



Optical properties:

Enhanced total & diffuse Transmission (Haze)

→ Better quantum efficiency (for a-Si) on ZnO compared to Asahi SnO₂

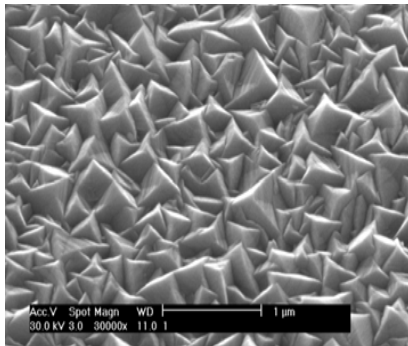


Highest stabilized efficiency for a-Si:H p-i-n on LPCVD ZnO (confirmed)

IMT Neuchâtel 2003:

$\eta = 9.47\%$ stabilized (with ARC)

single-junction a-Si:H p-i-n with
“modified” LPCVD ZnO process

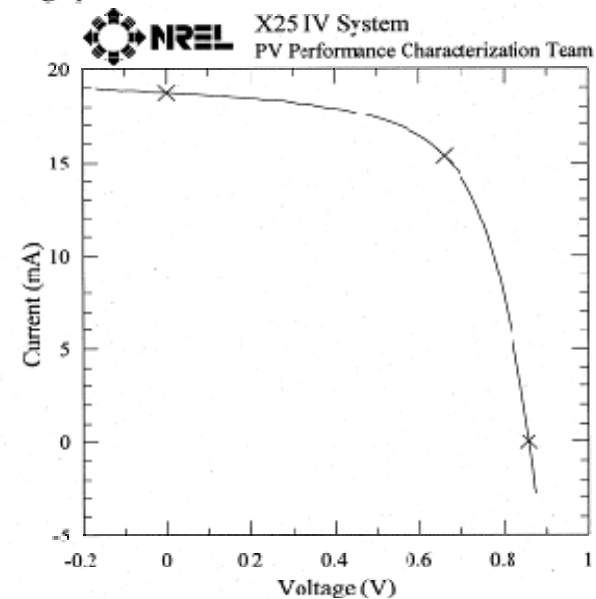


(J. Meier et al., WCPEC-3, Osaka 2003)

Our Motivation !

University of Neuchatel (Switzerland)
a-Si Cell

Device ID: C170103 Device Temperature: 25.0 ± 1.0 °C
Apr 21, 2003 15.12 Device Area: 1.070 cm²
Reporting Spectrum: AM1.5 Global Irradiance: 1000.0 W/m²



$V_{oc} = 0.3585\text{ V}$
 $I_{sc} = 18.739\text{ mA}$
 $J_{sc} = 17.519\text{ mA/cm}^2$
Fill Factor = 62.96%

$I_{max} = 15.365\text{ mA}$
 $V_{max} = 0.6592\text{ V}$
 $P_{max} = 10.128\text{ mW}$
Efficiency = 9.47%

In 2003:

Bottle-necks: **up-scaling to 1 m²**

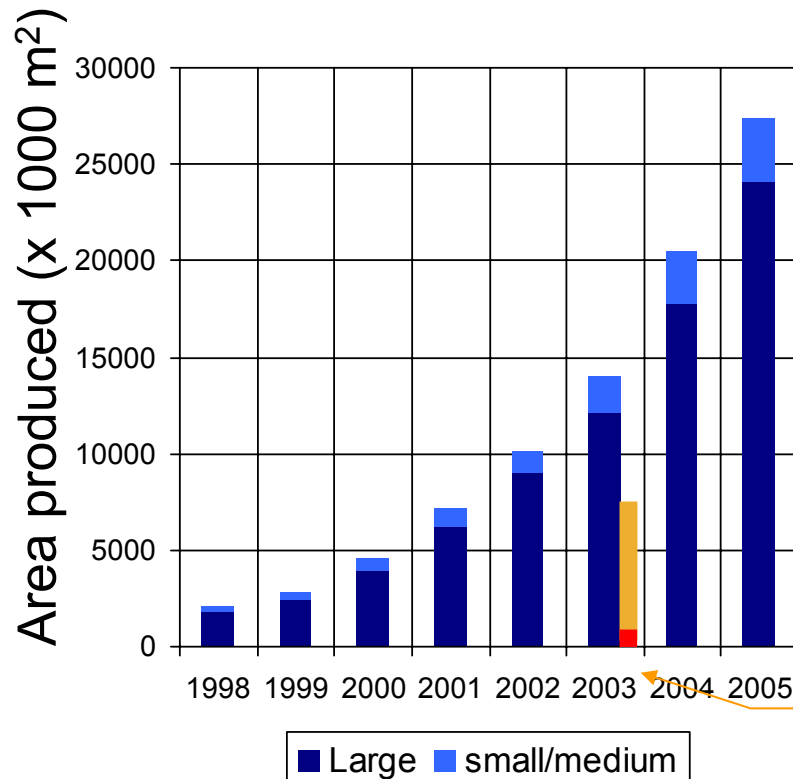
- availability of production system
- high investment cost and high risk

Thin film silicon PV technology developed at IMT

search for industrialisation partner

Find Synergies for large-area deposition

In 2003: AM-LCDs: Strong growth



From 22 bn\$ to 48 bn\$ in 2005
Monitor and TV will be the main driver

Solar cells:
c-Si: ~7 km²
Thin film: ~0.6km²

Mio Units	2000	2005
Mobile	380	460
Laptops	24	47
Monitors	6	90
TVs	0.2	7

Source :Nikkei Microdevices FPD 2002 yearbook
and Display search 2003 feb

2003

Oerlikon founds own R&D lab and enters thin film silicon PV



Why Neuchâtel?
Close to IMT and CRPP/EPFL
(strategic partners)

Goal: Process Transfer from Lab to Production

Oerlikon Solar-Lab, Puits-Godet 12a,
Neuchâtel:

- complete R&D Lab (clean/grey room)
- LPCVD system for ZnO deposition
- PECVD system for silicon deposition
- Laser scribing system
- Cell characterisation
- cleaning, glass cutting, gas delivery systems etc.

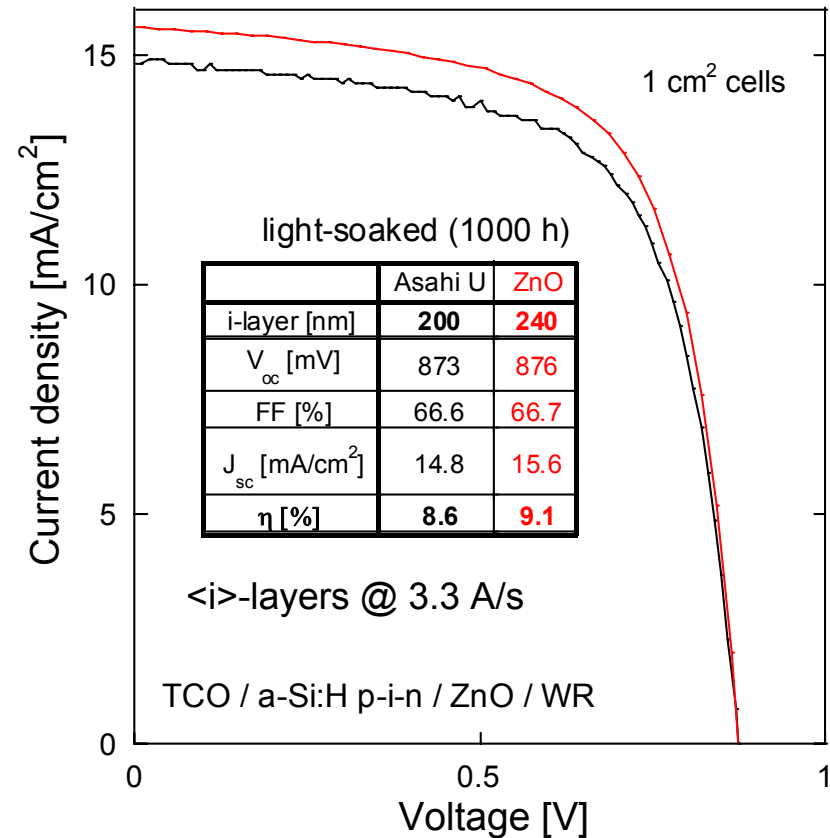
Today Oerlikon Solar-Lab SA have
21 employees working in a Lab of
about 550 sqm surface

Optimization of devices & deposition processes

a-Si:H p-i-n test cells

**9.1 % stabilized
a-Si:H p-i-n on ZnO**

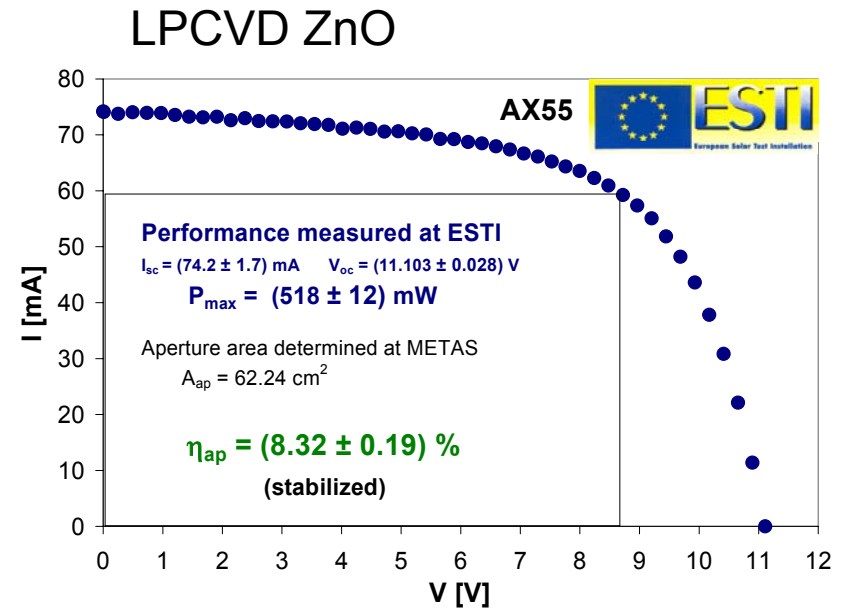
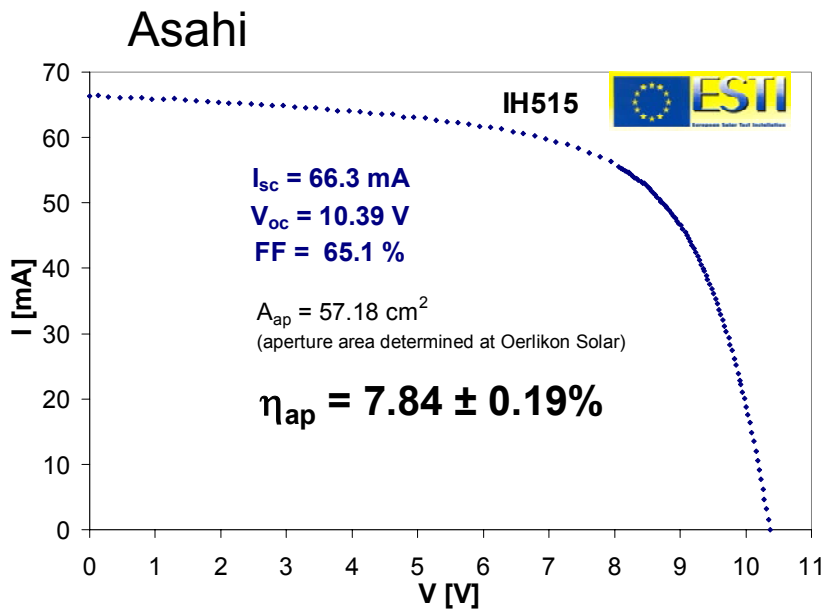
Update at 24th EU PVSEC
Hamburg, September 2009 !



S. Benagli et al., 23rd EUPVSEC Valencia (2008)

Up-scaling to 10x10 cm² mini-modules in KAI-M

Characterisation by ESTI of JRC in Ispra



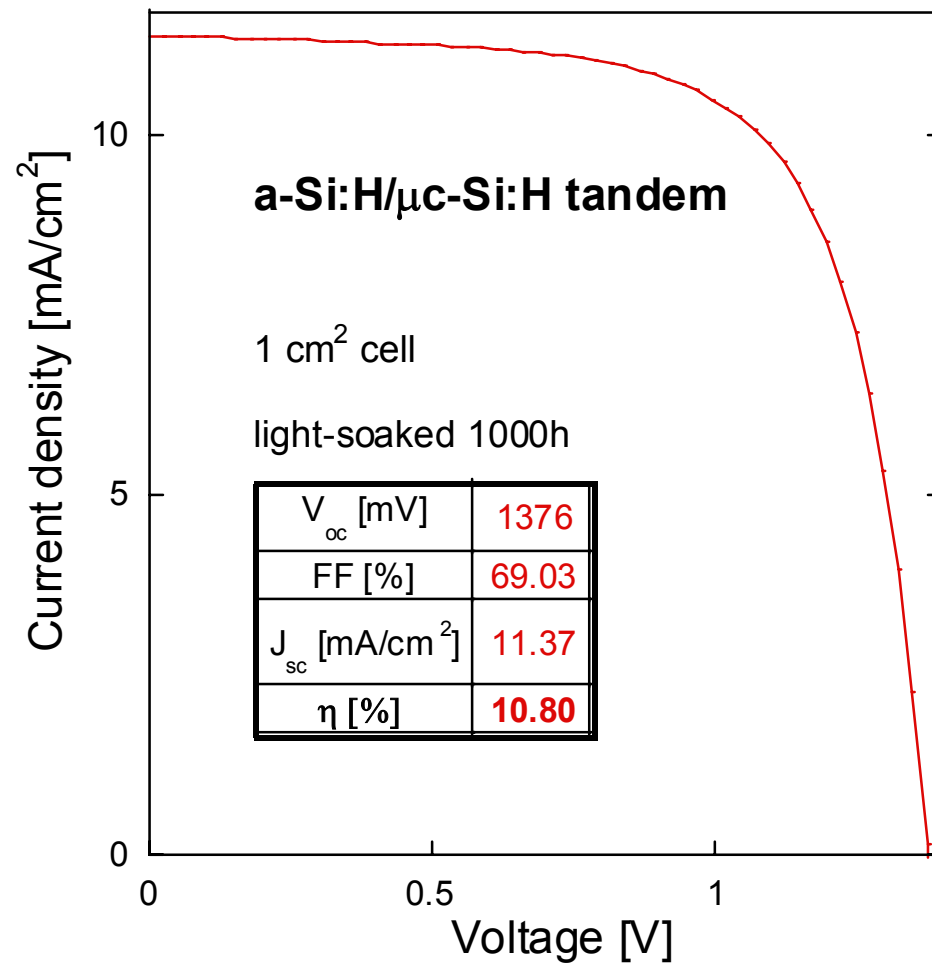
→ **0.5 % abs. enhanced stabilized efficiency compared to Asahi SnO₂**
~1 % abs. compared to commercial TCO

Best lab Micromorph tandem cell (light-soaked)

SnO₂ Asahi glass substrate

Best cell

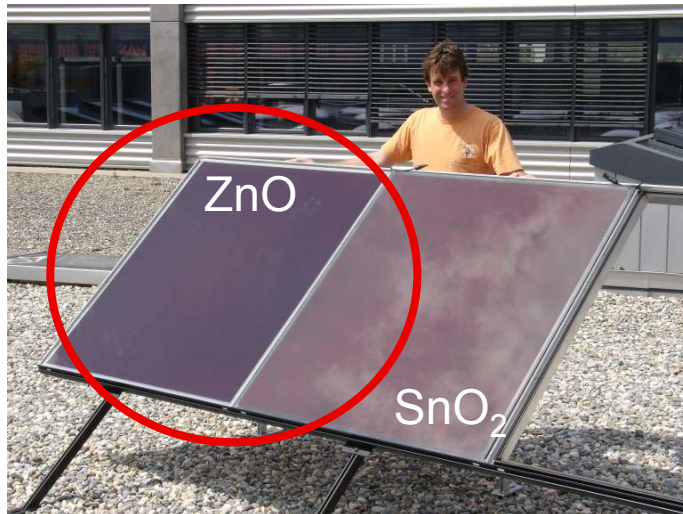
10.8 % stable efficiency



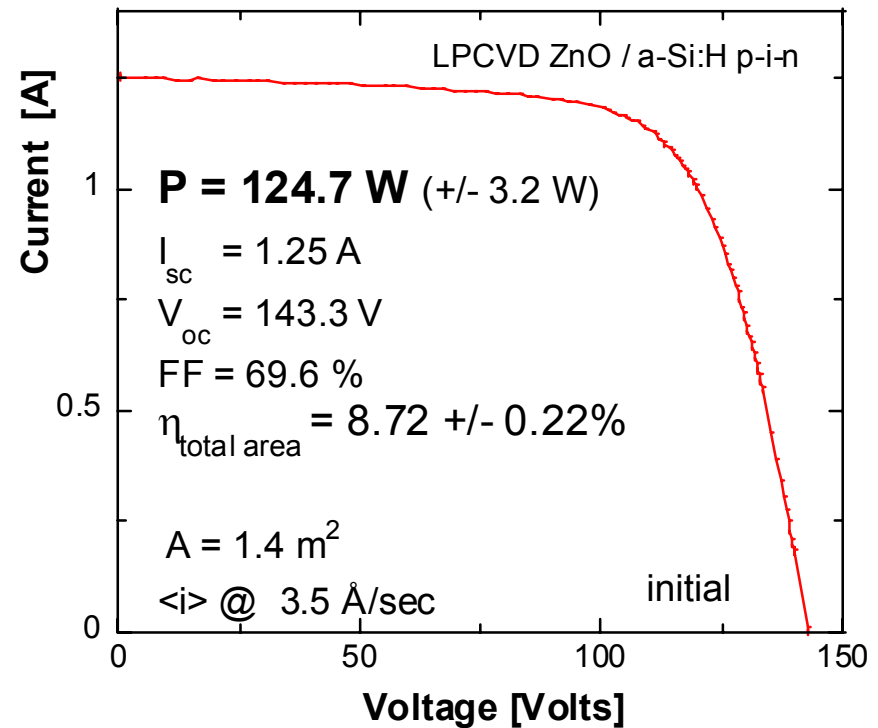
Scaling up in R&D Pilot line / Trübbach

a-Si:H p-i-n single-junction R&D module on ZnO: **124.7 W** (ini.)

Confirmed by ESTI of JRC Ispra



Industrial size 1.1x1.3 m² module on front LPCVD ZnO



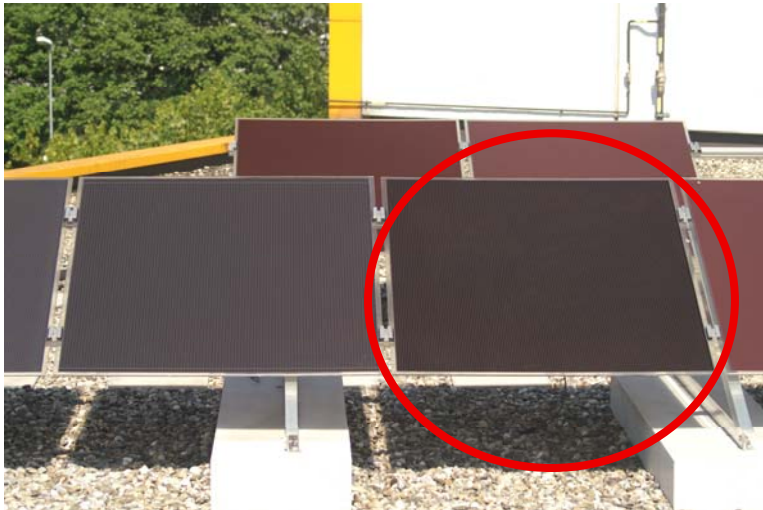
>100 W stabilized expected

➔ Still room for further improvements!

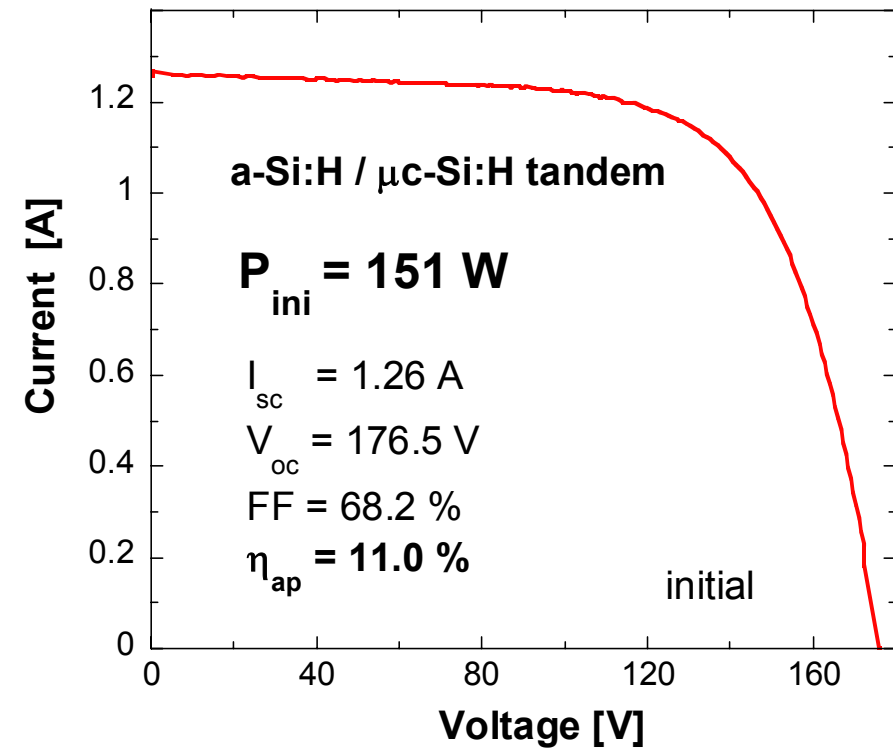
Micromorph Module 1.4 m²

R&D Pilot line in Trübbach:

151 W initial 1.4 m² module !



Industrial size 1.1x1.3 m² module
on in-house front LPCVD ZnO



→ Still room for further improvements!

CTI Projects of Oerlikon Solar from start until now

- **CRPP/EPFL: CTI 9675.2 running**

A new low ion energy bombardment PECVD reactor for the deposition of thin film silicon for solar cell applications

- **IMT CTI 8968.3 running**

Development of a novel surface treatment of LP-CVD ZnO layers used as Transparent Conductive Oxide for thin film silicon solar cells.

- **CRPP/EPFL: CTI 6947.1 EBS-IW finished**

A new large area very high frequency reactor for the high rate deposition of microcrystalline silicon for thin film solar cell applications

- **IMT: Eureka 7253.2 EPRP-IW finished**

Stability of advanced LP-CVD ZnO within encapsulated thin film silicon solar cells

- **IMT: CTI 6928.1 IWS-IW finished**

High rate deposition of microcrystalline silicon layers and cells

- **NTB (Neues Technikum Buchs): KTI Nr. 7112.2 EPRP-IW finished**

Development of QE measuring system

Oerlikon Solar

Segment Overview

Solar key member of the group with global footprint



800 employees worldwide

280 global support

300 scientists and engineers

20 locations in 11 countries

Over CHF 23m R&D investment in 2007

Over 350 living patents

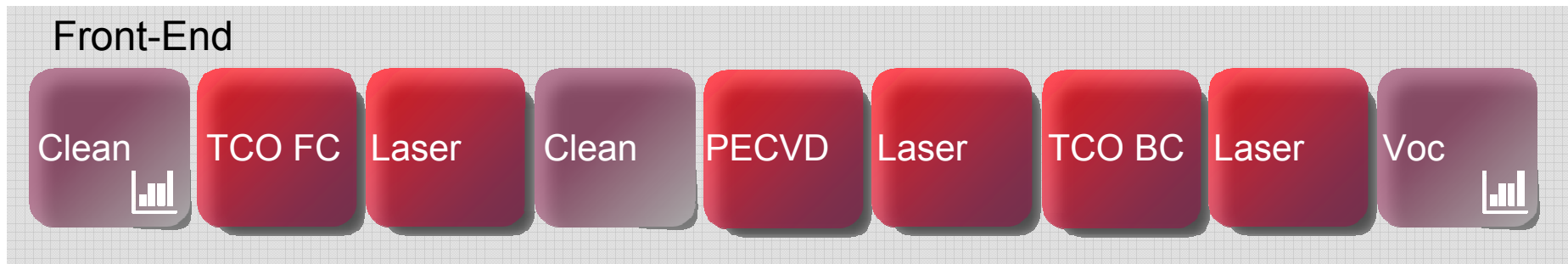
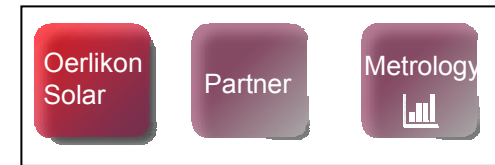
Over 900 000 modules produced by
customers of Oerlikon Solar

Oerlikon Solar

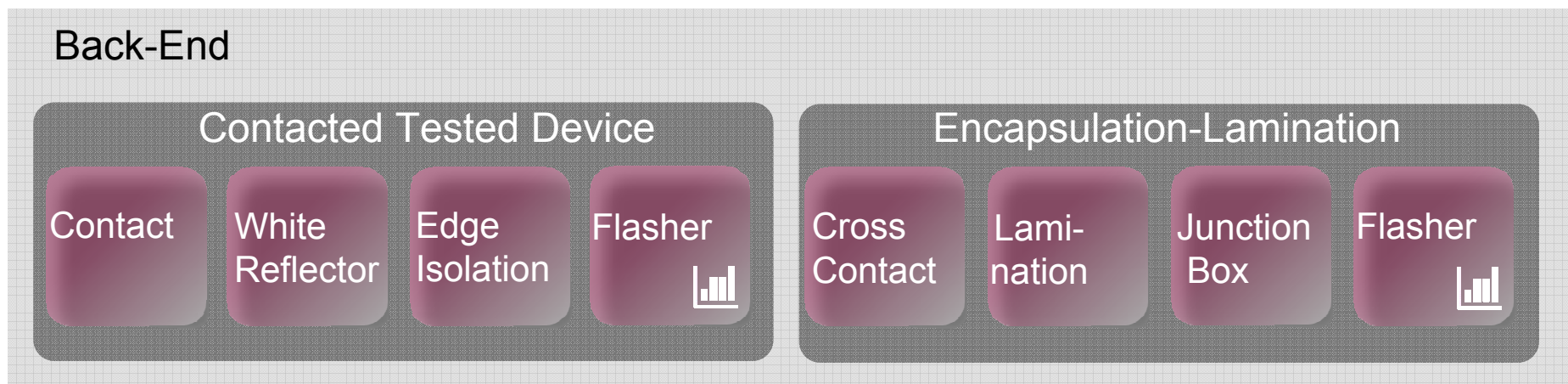
Equipment manufacturer for cost-effective production solutions for thin film silicon solar modules



Oerlikon provides end-to-end (E2E)
production solutions...



Line Automation



Oerlikon Solar Manufacturing Systems



TCO 1200

Transparent conductive oxide deposition



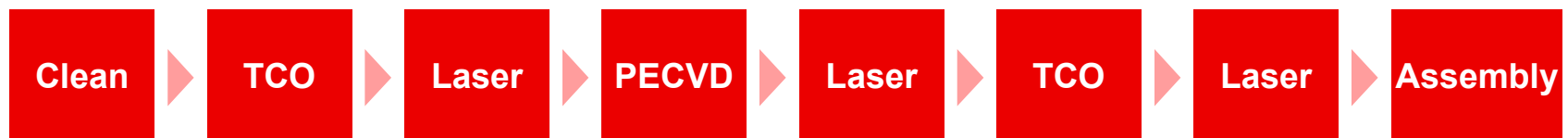
KAI 1200

Photovoltaic layer deposition

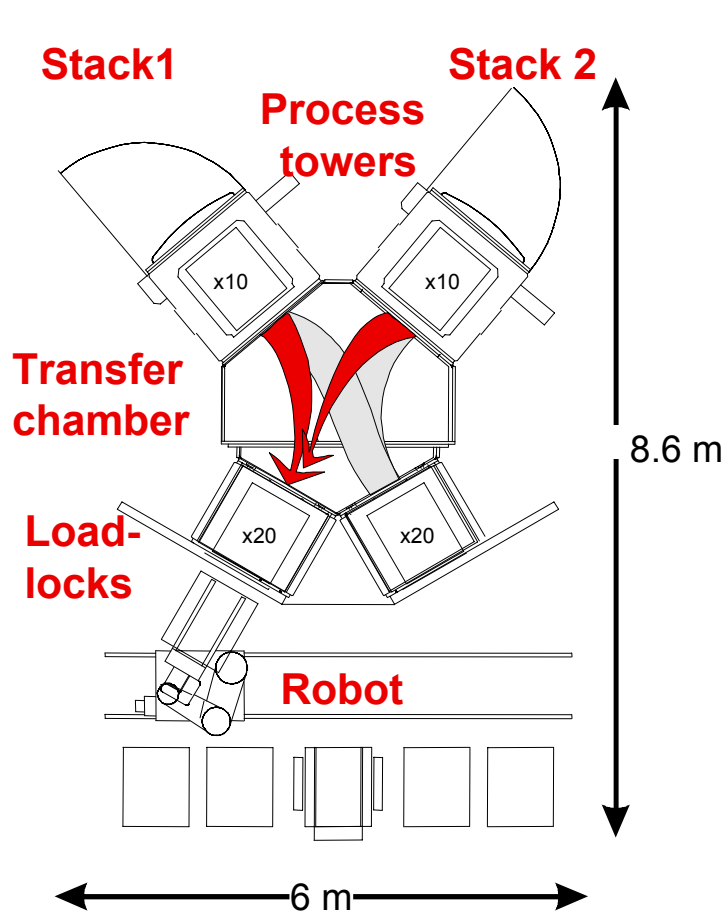


LSS 1200

Laser scribing

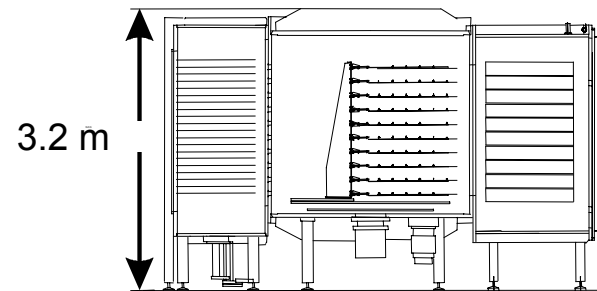


KAI System Concept - Parallel Processing of 20 reactors



KAI 20-1200

- Excitation frequency 40.68 MHz to significantly enhance deposition rate



- 2 process towers with 10 reactors in each stack
- 2 load-locks
- 1 transfer chamber
- External robot for glass loading from cassette

Highest productivity on small footprint: 20 MW_p / y for a-Si:H

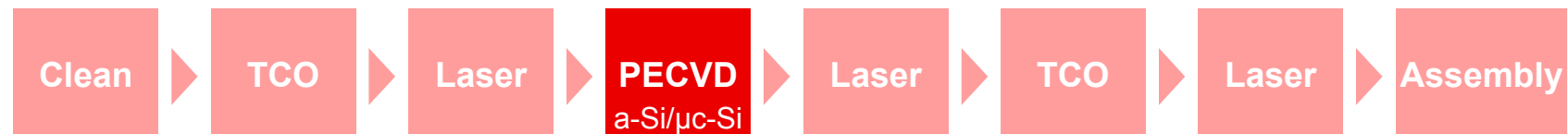
KAI 1200 - Proven Product for PV Layers

KAI 1200 with Plasma Box[®] reactor

- 40.68 MHz for higher rate & quality
- a-Si:H & $\mu\text{c-Si:H}$ p-i-n layers
- Single-chamber process
- Auto-clean after every run

Result

- High film quality
- High throughput
- High system flexibility & utilization
- Small footprint



Front and back view photo of KAI 20-1200



TCO 1200 - Higher Efficiency and Lower COO

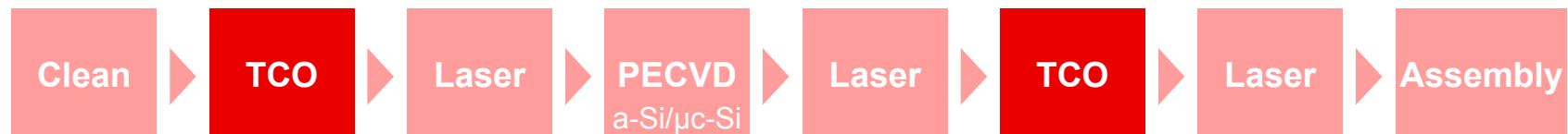


Proprietary LPCVD technology

- High conductivity
- Transparent conductor deposition and texturing in a single step

Integral to Micromorph process

- High transmission in visible and near IR light spectrums



Project update

Customer	Technology	Type	Contract Signed	Move-In On-Time	SOP On-Time	MW
Bosch/Ersol	Amorphous	Equipment	✓	✓	✓	40
Schüco	Amorphous	Equipment	✓	✓	✓	R&D
Schott	Amorphous	Equipment	✓	✓	✓	40
CSG	Amorphous	Equipment	✓	✓	✓	20
Sun Well	Amorphous	End-to-End	✓	✓	✓	50
Inventux	Micromorph®	Equipment	✓	✓	✓	30
HelioSphera	Micromorph®	End-to-End	✓	✓		30
Tianwei	Amorphous	End-to-End	✓	✓		46
Auria Solar	Micromorph®	End-to-End	✓	✓		60
Pramac	Micromorph®	End-to-End	✓	✓		30
Sun Well (2)	Micromorph®	End-to-End	✓			60
Sun Well (3)	Micromorph®	End-to-End	✓			120
Gadir	Amorphous	End-to-End	✓			40
Chint	Micromorph®	Equipment	✓			40

Total more than 600 MW

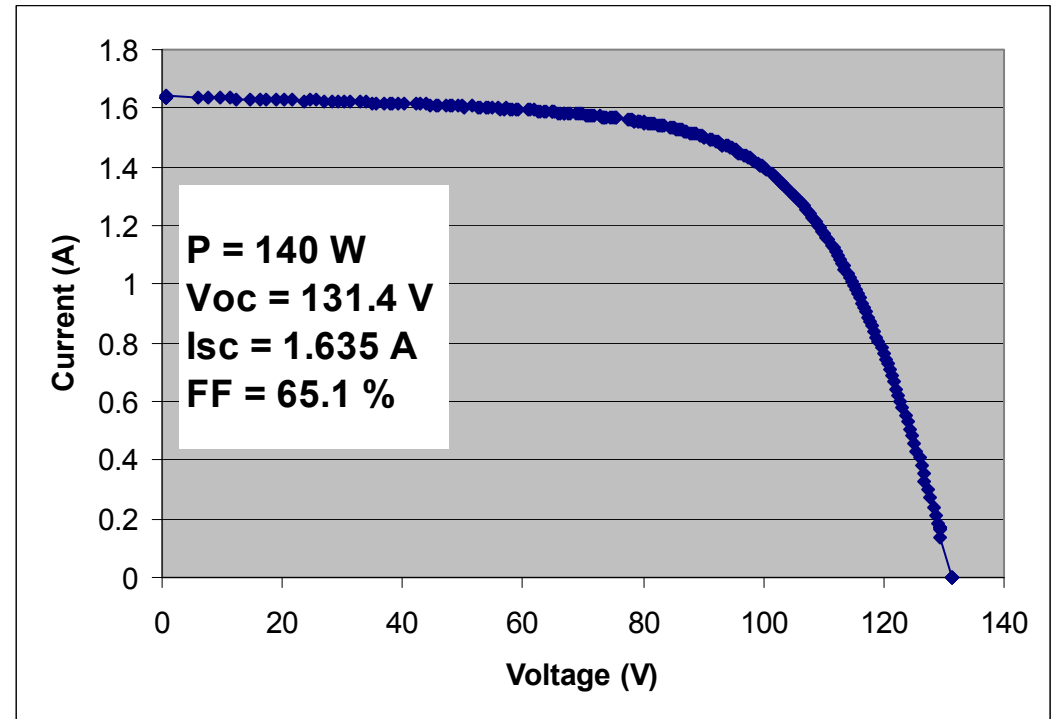
1st Micromorph line in Berlin

inventux[®]
SOLAR TECHNOLOGIES

Mass production line at Inventux –
best Micromorph modules



140 W initial module power (April'09)



Operational silicon thin film fields

3.4 MWp a-Si installation (Zahna, Germany)

- 39,000 thin film modules & 747 trackers
- Start of operation: 19 February 2009
- System integrator: AC Energy GmbH & Co. KG



1.3 MWp a-Si installation (Zahna, Germany)



Perspectives & Opportunities

Nice example from basic research to mass production

Success recipe:

- Partners with commitments
- Long-term support for basic research (OFEN, CTI)
- Well-trained experts & specialists

Oerlikon Solar:

- Proven solutions for high volume solar module production with more than 900'000 produced panels
- Oerlikon Solar is well-placed for the challenges of the coming PV century



Thank you
for your attention.

